

MF Square Wave Intermediate Frequency Sputtering Power Supply

Product Code: Intermediate frequency
sputtering power supply

Weight: 55.00kg

Dimensions: 0.00cm x 0.00cm x 0.00cm



Short Description

This unit is used for double cathode sputtering of metal or semiconductor materials, especially suitable for reactive magnetron sputtering, oxide nitride, carbide films to increase the ionization rate.

Description

MF Square Wave Mid Frequency Sputtering Plasma Power Supply

It is used in double cathode sputtering of metal or semiconductor material, especially in reactive magnetron sputtering, to increase the ionization rate of oxide, nitride and carbide films.

Features:

The main circuit topology adopts PFC + full-bridge architecture combined with DSP + FPGA digital control technology.

Constant power/constant current mode switching Constant power mode can better ensure the repeatability of the coating process

Built-in arc extinction time setting 10 us-100 us to adapt to different processes and target

materials arc display count

At the same time, V-ARCI-ARC is detected to quickly cut off the output and start the built-in patented technology to eliminate residual arc energy, avoid cathode and substrate arcing, and ensure high-precision film.

The independent main control system adopts intelligent current sharing technology to ensure that each module outputs the same power frequency in parallel, which effectively improves the reliability of the power supply system.

Configuration panel operation and display; remote PLC control

Communication interface: Analog; Modbus; PROFIBUS; EtherCAT